WHAT IS CLAIMED IS:

1. A pellicle comprising a thin film optimized for transmission of off-axis incident light at a desired angle.

2. The pellicle of Claim 1, further comprising an optical thickness greater than a design thickness by less than or equal to approximately one-quarter of an exposure wavelength.

3. The pellicle of Claim 1, wherein the thin film produces a transmission maxima at a wavelength between approximately one nanometer and approximately twenty nanometers above an exposure wavelength.

4. The pellicle of Claim 1, further comprising an anti-reflective coating disposed on at least one of a top surface and a bottom surface of the thin film, the anti-reflective coating producing a transmission maxima at a wavelength between approximately one nanometer and approximately twenty nanometers above an exposure wavelength.

5. The pellicle of Claim 4, wherein the anti-reflective coating includes a thickness between approximately one-quarter of an exposure wavelength and approximately one-half of an exposure wavelength.

6. The pellicle of Claim 1, further comprising a plurality of adjoining anti-reflective coatings disposed on at least one of a top surface and a bottom surface of the thin film, each of the anti-reflective coatings including a different refractive index.

7. A pellicle comprising a thin film including an optical thickness greater than a design thickness that produces a transmission maxima for normal incidence light at an exposure wavelength, the optical thickness optimized for transmission of off-axis incident light at a desired angle.

8. The pellicle of Claim 7, further comprising the optical thickness greater than the design thickness by less than or equal to approximately one-quarter of the exposure wavelength.

9. The pellicle of Claim 7, wherein the thin film produces a transmission maxima at a wavelength between approximately one nanometer and approximately twenty nanometers above the exposure wavelength.

10. The pellicle of Claim 7, further comprising an anti-reflective coating disposed on a top surface and a bottom surface of the thin film.

11. The pellicle of Claim 10, wherein the anti-reflective coating includes a first refractive index approximately equal to the square root of a second refractive index associated with the thin film.

12. The pellicle of Claim 10, wherein the anti-reflective coating produces a transmission maxima at a wavelength between approximately one nanometer and approximately twenty nanometers above the exposure wavelength.

13. The pellicle of Claim 10, wherein the anti-reflective coating includes a thickness between approximately one-quarter of the exposure wavelength and approximately one-half of the exposure wavelength.

14. The pellicle of Claim 7, further comprising a plurality of adjoining anti-reflective coatings disposed on a top surface and a bottom surface of the thin film, each of the anti-reflective coatings including a different refractive index.

15. The pellicle of Claim 7, wherein the thin film comprises an amorphous fluoropolymer.

16. The pellicle of Claim 7, wherein:

the thin film includes a thickness of approximately 855 nanometers; and

the exposure wavelength is between approximately 248 nanometers and approximately 436 nanometers.

17. A photolithography system for optimizing off-axis transmission of light, comprising:

a photomask; and

a pellicle comprising:

a frame coupled to the photomask; and

a thin film operable to transmit approximately ninety-nine percent (99%) of off-axis light at an exposure wavelength, the thin film including an optical thickness greater than a design thickness that produces a transmission maxima for normal incidence light at the exposure wavelength.

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18. The system of Claim 17, further comprising the optical thickness greater than the design thickness by less than or equal to approximately one-quarter of the exposure wavelength.

19. The system of Claim 17, wherein the thin film produces a transmission maxima at a wavelength between approximately one nanometer and approximately twenty nanometers above the exposure wavelength.

20. The system of Claim 17, further comprising an anti-reflective coating disposed on a top surface and a bottom surface of the thin film, the anti-reflective coating including a thickness between approximately one-quarter of the exposure wavelength and approximately one-half of the exposure wavelength.

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21. The system of Claim 20, wherein the anti-reflective coating produces a transmission maxima at a wavelength between approximately one nanometer and approximately twenty nanometers above the exposure wavelength.

22. The system of Claim 20, wherein the anti-reflective coating includes a first refractive index approximately equal to the square root of a second refractive index associated with the thin film.

23. The system of Claim 17, further comprising a plurality of adjoining anti-reflective coatings disposed on a top surface and a bottom surface of the thin film, each of the anti-reflective coatings including a different refractive index.

24. The system of Claim 17, wherein the frame comprises aluminum.

25. The system of Claim 17, wherein the thin film comprises an amorphous fluoropolymer.

26. A method for performing photolithography, comprising:

forming a thin film with an optical thickness greater than a design thickness that produces a transmission maxima for normal incidence light at an exposure wavelength, the optical thickness optimized for transmission of off-axis incident light at a desired angle;

attaching the thin film to a frame to form a pellicle;

mounting the pellicle to a photomask; and

exposing the pellicle and the photomask to radiant energy having the exposure wavelength.

27. The method of Claim 26, further comprising coating a top surface of the thin film with an anti-reflective material, the anti-reflective material including a thickness between approximately one-quarter of the exposure wavelength and approximately one-half of the exposure wavelength.

28. The method of Claim 27, further comprising coating a bottom surface of the thin film with the anti-reflective material.

29. The method of Claim 26, wherein the thin film produces a transmission maxima at a wavelength between approximately one nanometer and approximately twenty nanometers above the exposure wavelength.

30. The method of Claim 26, further comprising coating at least one of a top surface and a bottom surface of the thin film with a plurality of adjoining layers of anti-reflective material, each layer including a different refractive index.